

Welcoming Remarks

The 4th Workshop on Reactive Metal Processing subtitled “Recent Progress in Materials Processing” is being held at the Massachusetts Institute of Technology (MIT) in Boston from March 14 to 16, 2007; this follows the 1st Workshop held in Boston (March 17–19, 2006), the 2nd Workshop held in Tokyo (November 17–19, 2006), and the 3rd Workshop held in Boston (March 2–3, 2007). The workshop is jointly organized by the Sadoway Laboratory at MIT and the Okabe Laboratory at the University of Tokyo (UT). We extend our warmest welcome to all participants for the 4th Workshop.

The remarkable shift in thinking towards sustainability has prompted a worldwide renewed interest in developing new processes as well as a greater demand for advanced engineering technology and highly-functional materials in industrial products. In particular, materials processing has attracted significant attention from both industrial firms and academic scientists. This workshop reflects the current circumstances in reactive metal processing.

The main intention of the workshop is to discuss the recent progress in the fields of reactive metal processing and simultaneously to create and develop an active and global partnership between industries and academia in this field. In the previous three workshops, totally 50 excellent lectures by world-leading researchers and young graduate students from 7 countries were given on a wide variety of aspects from process fundamentals to operational practices about reactive metal processing. The 4th Workshop intends to continue the practice of giving younger researchers the opportunity to present their recent research findings and to provide them with an international forum for exposure to current thinking about the field.

We hope you will find the 4th Workshop fruitful and enjoyable and are able to establish new partnerships as well as strengthen old ones. Finally, we express our sincere appreciation to all the participants for their scientific contributions and to the administrative staffs and students of the UT and MIT for their assistance.



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